

StealthTM

Patent No.10-2019-0088245/10-2020-0021111

Stealth-1

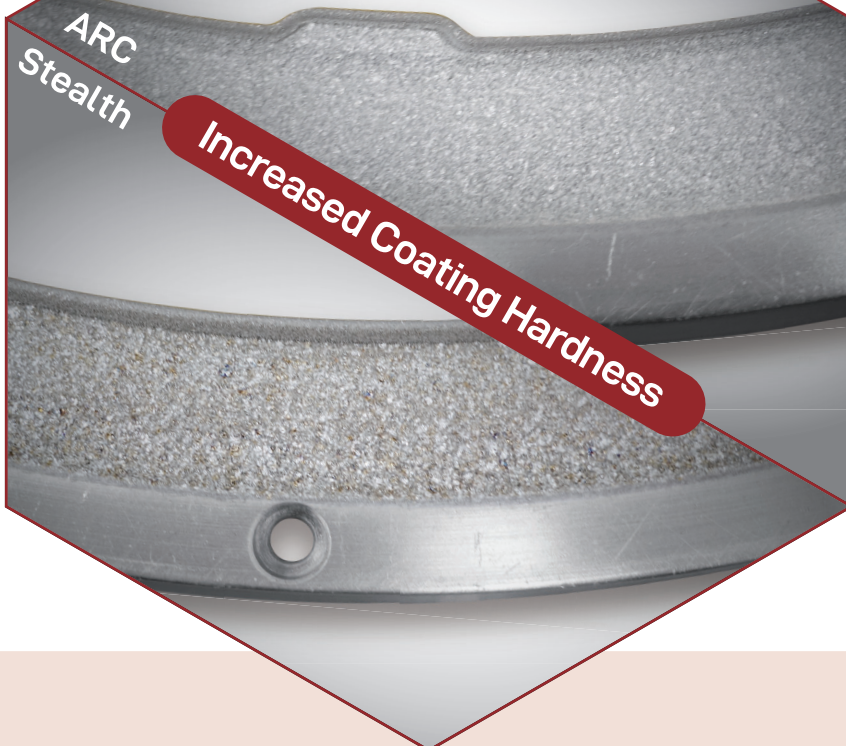
COATING

Benefits



It is possible to suppress abnormal peeling by improving the deposition of sputtering particles (thin film material) dispersed on the inner wall of the chamber during the PVD process.

By using A+a (additive) wire with the preexisting ARC coating method, it is possible to increase the coating hardness by more than 16 times, thereby reducing abnormal peeling caused by hard deposition of the depo film.



CINOS Metal Coating Trend

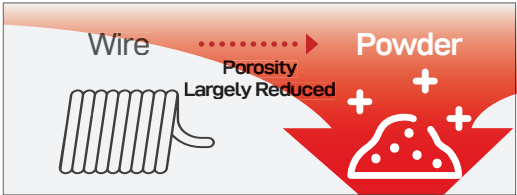
Metal coating technology has been developed according to semiconductor integration, and it is possible to provide coatings that meet customer needs depending on the development of Al+a (additive) wire, powder coating technology, and the degree of semiconductor integration.

We have the technology to form high roughness such as the roughness of 1200, 1400, 4000 μ inch for Al ARC coating to extend the lifespan of semiconductor equipment.

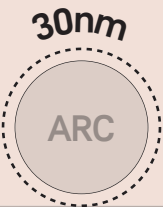
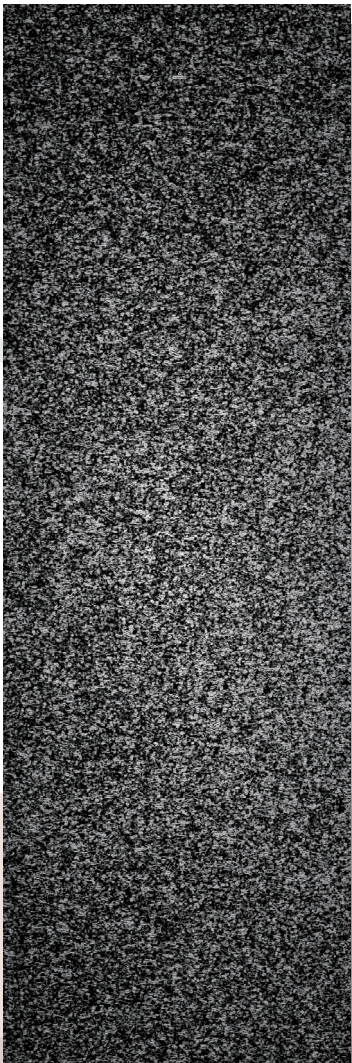
It is very important to form a surface structure, and with the structure, it is possible to prevent contamination and defects on the thin film that are deposited on one side of the substrate during sputtering.

Stealth-2

COATING



Stealth-2 Coating uses A+a (additive) powder and shows hardness characteristics similar to the stealth coating, and the porosity of the coating is greatly reduced, thereby reducing outgassing and back-up time during process use.



Al Wire



Al+ α Wire



Al+ α Powder

Advanced Hardness & Porosity Property

Performance
Technology
Quality

CINOS



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